



Discharge physics of inductively coupled plasmas

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Inductively coupled plasmas (ICPs) have been widely used in various applied fields, such as semiconductor/display/solar-cell processing (etching, deposition, and ashing), wireless light lamp, nanostructure fabrication, nuclear-fusion operation, spacecraft propulsion, gas reformation, and the removal of hazardous gases and materials and thus, fundamental understanding on the discharge physics of ICPs is highly important. In this talk, representative discharge physics of the ICPs, such as electron heating mechanism, E-H mode transition and hysteresis, gas heating, and RF bias effects will be presented [1-14].

References

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